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# **Room-temperature ferroelectricity** in strained SrTiO<sub>3</sub>

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Systems with a ferroelectric to paraelectric transition in the vicinity of room temperature are useful for devices. Adjusting the ferroelectric transition temperature  $(T_c)$  is traditionally accomplished by chemical substitution—as in  $Ba_xSr_{1-x}TiO_3$ , the material widely investigated for microwave devices in which the dielectric constant ( $\epsilon_r$ ) at GHz frequencies is tuned by applying a quasi-static electric field<sup>1,2</sup>. Heterogeneity associated with chemical substitution in such films, however, can broaden this phase transition by hundreds of degrees<sup>3</sup>, which is detrimental to tunability and microwave device performance. An alternative way to adjust  $T_c$  in ferroelectric films is strain<sup>4–8</sup>. Here we show that epitaxial strain from a newly developed substrate can be harnessed to increase  $T_c$  by hundreds of degrees and produce room-temperature ferroelectricity in strontium titanate, a material that is not normally ferroelectric at any temperature. This strain-induced enhancement in  $T_{\rm c}$  is the largest ever reported. Spatially resolved images of the local polarization state reveal a uniformity that far exceeds films tailored by chemical substitution. The high  $\epsilon_r$  at room temperature in these films (nearly 7,000 at 10 GHz) and its sharp dependence on electric field are promising for device applications<sup>1,2</sup>.

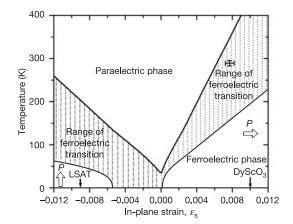
Enormous strains can be imparted to thin films and have previously been used to alter the  $T_c$  of ferromagnetic<sup>9,10</sup> and super-

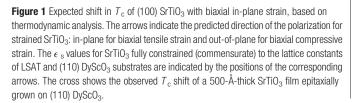
conducting<sup>11–13</sup> materials. For such phenomena, strain-induced enhancements in  $T_c$  as large as tens of degrees have been observed<sup>9</sup>. Owing to the strong coupling between strain and ferroelectricity, much larger  $T_c$  shifts are expected<sup>4,6</sup>, and have been observed<sup>7,8</sup>, in ferroelectric materials.

In its pure, unstressed form, strontium titanate (SrTiO<sub>3</sub>) is an incipient ferroelectric. It remains paraelectric down to 0 K, although chemical<sup>14,15</sup> or isotopic substitution<sup>16</sup>, as well as the application of stress<sup>4</sup>, easily disturb this delicate state, resulting in ferroelectricity. The boundary conditions imposed by a substrate profoundly affect ferroelectricity in thin films. Figure 1 shows the predicted<sup>4</sup> shift in T<sub>c</sub> for SrTiO<sub>3</sub> (ref. 17) under biaxial strain  $\epsilon_s = (a_{\parallel} - a_0)/a_0$ , where  $a_0$ is the lattice parameter of free-standing  $SrTiO_3$  and  $a_{\parallel}$  is the in-plane lattice parameter of a biaxially strained (100) SrTiO<sub>3</sub> film. The hatched region shows the range in predicted  $T_c$  due to the spread in reported property coefficients for SrTiO<sub>3</sub> (refs 18, 19) that enter into the thermodynamic analysis. For example, for positive  $\epsilon_s$  and T > 120 K, the enhancement in  $T_c$  is given by  $\Delta T_c = 2\epsilon_s \epsilon_0 C(Q_{11} + Q_{12})/(s_{11} + s_{12})$ , where  $\epsilon_0$  is the permittivity of free space, C is the Curie constant,  $Q_{11}$  and  $Q_{12}$  are the electrostrictive coefficients, and  $s_{11}$  and  $s_{12}$  are elastic compliances of SrTiO<sub>3</sub>. The breadth of the hatched region in Fig. 1 for  $T_c$  is mainly due to the nearly factor-of-two variation in the ratio of  $(Q_{11} + Q_{12})/(s_{11} + s_{12})$  for what are considered the most accurate reported values of these constants. These predictions imply that a biaxial tensile strain of order 1% will shift the  $T_c$  of SrTiO<sub>3</sub> to the vicinity of room temperature.

In practice, the synthesis of uniformly strained ferroelectric films is challenging. Epitaxial ferroelectric films are usually grown to thicknesses greatly exceeding their critical values, resulting in undesirable relaxation towards a zero-strain state by the introduction of dislocations. Dislocation densities of  $\sim 10^{11}$  cm<sup>-2</sup> are typical in epitaxial Ba<sub>x</sub>Sr<sub>1-x</sub>TiO<sub>3</sub> films<sup>20</sup>, and the resulting inhomogeneous strain further smears the phase transition, in addition to the effects of chemical heterogeneity mentioned above. Our approach to controlling the properties of ferroelectric SrTiO<sub>3</sub> films centres on the development of new substrates that enable the growth of uniformly strained films below, or at least far closer to, the critical thickness for relaxation.

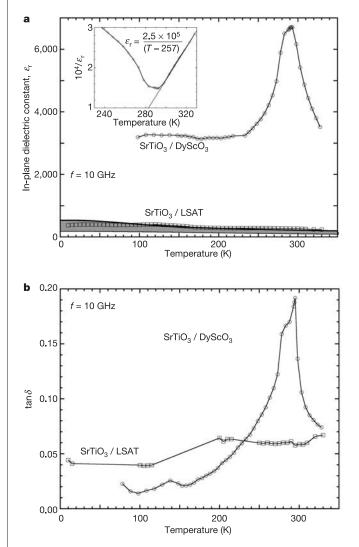
Depending on the choice of substrate, films may be grown under compressive or tensile strain. Commercially available substrates that





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are larger than SrTiO<sub>3</sub>, such as KTaO<sub>3</sub>  $(a = 3.989 \text{ Å})^{21}$  or MgO  $(4.212 \text{ Å})^{21}$ , are unsuitable for high-quality SrTiO<sub>3</sub>  $(a = 3.905 \text{ Å})^{18}$  growth because of their excessively large lattice mismatches (2.2% and 7.7%, respectively). On such substrates dislocation introduction commences soon after film nucleation, and films typically have very large mosaic spread. As the critical thickness at which dislocations begin to form varies approximately inversely with lattice mismatch, lower mismatch is desired to allow strained, low-dislocation density SrTiO<sub>3</sub> films to be grown that are thick enough to allow their ferroelectric properties to be conveniently probed. To produce a closer lattice match, we have developed single crystals of a new substrate material, DyScO<sub>3</sub>, for the growth of SrTiO<sub>3</sub> films under uniform biaxial tensile strain. DyScO<sub>3</sub> is orthorhombic with lattice constants<sup>22</sup> a = 5.440 Å, b = 5.713 Å,



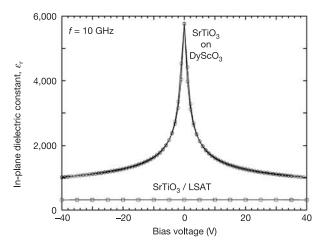
**Figure 2** In-plane dielectric constant ( $\epsilon_i$ ) and dielectric loss (tan $\delta$ ) in strained epitaxial SrTiO<sub>3</sub> films as a function of temperature and film thickness at a measurement frequency (*f*) of 10 GHz. **a**, **b**, Contrast of in-plane  $\epsilon_r$  and tan $\delta$ , respectively, of 500-Å-thick SrTiO<sub>3</sub>/(110) DyScO<sub>3</sub> and SrTiO<sub>3</sub>/(100) LSAT epitaxial films. These films are under biaxial tensile and compressive strain, respectively. The peak in  $\epsilon_r$  of about 7,000 and the simultaneous peak in tan $\delta$  indicate that the  $T_c$  of SrTiO<sub>3</sub> under biaxial tension of  $\epsilon_s = 0.008$  is about 293 K. The inset in **a** shows a Curie–Weiss fit to  $1/\epsilon_r$ . Owing to systemic errors involved in the measurement and calculation of the in-plane dielectric constant, the vertical scale in **a** may be off by as much as 10%. The shaded region in **a** corresponds to the expected value of the in-plane  $\epsilon_r$  for a SrTiO<sub>3</sub> film commensurately strained to LSAT ( $\epsilon_s = -0.009$ ), based on thermodynamic analysis and the range of relevant reported property coefficients for SrTiO<sub>3</sub> (refs 18, 19).

and c = 7.887 Å. It is not ferroelectric down to 4 K. The (110) DyScO<sub>3</sub> surface has a nearly square surface mesh with an inplane lattice spacing  $a_{\parallel} = 3.944$  Å, resulting in a tensile lattice mismatch at room temperature (25 °C) of +1.0% with (100) SrTiO<sub>3</sub>. For comparison, the commercial substrate (LaAlO<sub>3</sub>)<sub>0.29</sub> × (SrAl<sub>0.5</sub>Ta<sub>0.5</sub>O<sub>3</sub>)<sub>0.71</sub> (LSAT<sup>23</sup>, a = 3.869 Å) with a lattice mismatch of -0.9% at room temperature was also used to grow epitaxial (100) SrTiO<sub>3</sub> films under uniform compressive strain. The low dielectric constants of both DyScO<sub>3</sub> ( $\epsilon_{11} = 22.0$ ,  $\epsilon_{22} = 18.8$  and  $\epsilon_{33} = 35.5$ ) and LSAT ( $\epsilon_r = 22.5$ )<sup>24</sup> reduce field penetration in the substrate and facilitate modelling of the in-plane  $\epsilon_r$  of the SrTiO<sub>3</sub> films when interdigitated electrodes are used<sup>25</sup>, as in this study.

Reactive molecular beam epitaxy (MBE) was used to grow epitaxial SrTiO<sub>3</sub> films on both (110) DyScO<sub>3</sub> and (100) LSAT substrates. During growth the substrates were held at 650 °C and immersed in  $5.0 \times 10^{-7}$  torr (background pressure) of oxygen plus ~10% ozone. Reflection high-energy electron diffraction (RHEED) intensity oscillations were monitored to ensure that complete SrO and TiO<sub>2</sub> monolayers were deposited alternately to form the SrTiO<sub>3</sub> films<sup>26</sup>. Although many samples were grown and characterized, the properties of a 500-Å-thick film grown on each substrate are compared below to show the effect of strain state on the ferroelectric properties of SrTiO<sub>3</sub>.

X-ray diffraction scans show the out-of-plane lattice constant to be compressed  $(a_{\perp} = 3.88 \pm 0.01 \text{ Å})$  for the films grown on DyScO<sub>3</sub>, and extended  $(a_{\perp} = 3.93 \pm 0.01 \text{ \AA})$  for the films grown on LSAT, as expected from the boundary conditions imparted by the substrates. High-resolution X-ray diffraction measurements of the 500-Å-thick SrTiO<sub>3</sub> film grown on DyScO<sub>3</sub> reveal that its in-plane lattice constant at room temperature is  $a_{\parallel} = 3.935 \pm 0.002 \text{ A}$ , corresponding to 0.8% biaxial tensile strain. Its out-of-plane lattice constant is  $a_{\perp} = 3.8785 \pm 0.0005$  Å. Although somewhat beyond the critical thickness at which relaxation begins to occur, the rocking curve full-width at half-maximum (FWHM) of the 200 SrTiO<sub>3</sub> X-ray diffraction peak is 13 arcsec (0.004°), the narrowest ever reported for an epitaxial SrTiO<sub>3</sub> film. This, and other aspects of the X-ray scattering measurements, indicate that this film has a higher degree of uniformity and structural perfection than is typical of Ba<sub>x</sub>Sr<sub>1-x</sub>TiO<sub>3</sub> films. The rocking curve FWHM of the 200 SrTiO<sub>3</sub> peak of the 500-Å-thick SrTiO<sub>3</sub> film grown on LSAT was also quite narrow, 21.5 arcsec (0.006°).

Measurements of the complex dielectric permittivity were performed on the  $SrTiO_3$  films as a function of frequency (1–20 GHz), temperature (75–330 K), and direct current (d.c.) electric field



**Figure 3** Dielectric tunability of the same 500-Å-thick SrTiO<sub>3</sub> films grown on DyScO<sub>3</sub> and LSAT as shown in Fig. 2. The film grown on DyScO<sub>3</sub> shows 82% tuning between 0 and  $\pm 40$  V at room temperature, with slight hysteresis. The film grown on LSAT exhibits  $\sim 0\%$  tunability with the application of  $\pm 40$  V at room temperature.

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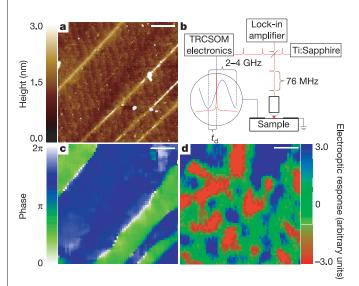
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(±40 V across 6 μm) using interdigitated electrodes. The 1–2-μmthick Ag interdigitated electrodes had 80-μm finger lengths and 6-μm finger gaps for the room-temperature measurements and 40-μm finger lengths and 12-μm finger gaps for the temperaturedependent measurements. The fingers were aligned parallel to the <110 > in-plane directions of the SrTiO<sub>3</sub> films.

Figure 2 shows the temperature-dependent in-plane<sup>25</sup>  $\epsilon_r$  and loss tangent, tanô, of the 500-Å SrTiO<sub>3</sub>/DyScO<sub>3</sub> film measured at 10 GHz. These data are from a device acting as a microwave varactor (a voltage-tunable capacitor) with 2:1 tuning, demonstrating the technological significance of these films. The curves agree well with expected Curie-Weiss behaviour (inset) for a uniformly strained film, exhibiting a maximum in  $\epsilon_{\rm r}$  and tanb at  $T_{\rm c}\approx 293\,{\rm K}$  and a Curie constant typical of displacive ferroelectrics. The peak  $\epsilon_r$  of nearly 7,000 at 10 GHz is higher and the width of the peak in  $\epsilon_r$ versus T is narrower than any value reported for  $Ba_{1-x}Sr_{x}TiO_{3}$  thin films. By contrast, SrTiO<sub>3</sub>/LSAT has a much lower dielectric constant and there is no peak in  $\epsilon_r$  versus T. This result is fully consistent with the biaxial strain state causing the ferroelectric polarization to lie in the plane of the film for SrTiO<sub>3</sub> on DyScO<sub>3</sub>, the direction sensed by the interdigitated electrodes, but lying out-of-plane of the SrTiO<sub>3</sub> grown on LSAT.

The observed  $T_c$  shift surpasses all prior records<sup>7,8</sup> and gives credence to prior work on SrTiO<sub>3</sub>/SrZrO<sub>3</sub> superlattices where ferroelectricity at room temperature in 8-nm-thick strained SrTiO<sub>3</sub> layers was assumed to be responsible for the dielectric properties of the composite superlattice<sup>27</sup>. Our results are consistent with a strain-induced phenomenon; the possibility that minute Sc doping from the DyScO<sub>3</sub> substrate is in part responsible for the dramatic changes in dielectric behaviour is also being investigated, although no such effects have ever been reported<sup>28</sup>.

The remarkable field sensitivity of  $\epsilon_r$ , which drops by 82% for an



**Figure 4** Comparison of the morphology and microwave electro-optic response of tunable dielectric films at room temperature (just above  $T_c$ ). The scale bars are 1  $\mu$ m for all images. **a**, An AFM image of the same 500-Å-thick SrTiO<sub>3</sub> film grown on DyScO<sub>3</sub> shown in Fig. 2. In addition to unit-cell-high steps on the surface of the SrTiO<sub>3</sub> film, four diagonal linear features that protrude ~50 Å from the surface are evident. Similar surface imperfections are seen on the bare substrates, suggesting that they are associated with polishing. **b**, Schematic of the TRCSOM technique used for imaging ferroelectric polarization at microwave frequencies. **c**, Images of the phase shift between the electro-optic response and microwave driving field (3.27 GHz) for the same SrTiO<sub>3</sub>/DyScO<sub>3</sub> film (but not the identical region) as in **a**, revealing uniform in-plane polarization separated by clear boundaries like the ones observed by AFM. **d**, TRCSOM image (at one time delay) of a typical epitaxial Ba<sub>0.5</sub>Sr<sub>0.5</sub>TiO<sub>3</sub>/MgO film at 2.06 GHz, showing inhomogeneous in-plane polarization.

applied voltage of 40 V across  $6 \,\mu$ m gaps, is shown in Fig. 3. Such large tuning with modest fields makes these films applicable to a variety of microwave applications. As is typical of ferroelectric thin films, their properties depend on thickness (Supplementary Information).

Optical measurements of the ferroelectric polarization at microwave driving fields were performed using time-resolved confocal scanning optical microscopy (TRCSOM)<sup>29,30</sup>. The in-phase and outof-phase response at the microwave driving frequency correspond to the real and imaginary parts of the polar contribution to the dielectric response at that frequency.

Figure 4c shows a typical TRCSOM image of the phase shift between linear electro-optic response and a microwave driving field (3.27 GHz), measured for the 500 Å SrTiO<sub>3</sub>/DyScO<sub>3</sub> film. The electro-optic phase is computed from a fit to the temporal response at various points in the microwave drive cycle<sup>29,30</sup>. Most striking are the large regions in which the phase is essentially uniform, separated by sharp boundaries at which the phase changes by 90° or 180°. These boundaries correspond to features observed by atomic force microscopy (AFM) on the film (Fig. 4a) as well as on bare DyScO<sub>3</sub> substrates, and may be due to surface imperfections that break the in-plane symmetry and produce an easy axis for the SrTiO<sub>3</sub> films. For sake of comparison, Fig. 4d shows a typical TRCSOM image (at a fixed time delay) for a ferroelectric film (Ba<sub>0.5</sub>Sr<sub>0.5</sub>TiO<sub>3</sub>/MgO) that has not been strain-engineered. The strong fluctuations in the electro-optic response on submicrometre scales are typical of films that are inhomogeneously strained.

The remarkable dielectric properties of  $SrTiO_3$ , while recognized for many decades, have previously only been accessible in the bulk and at cryogenic temperatures. Efforts to shape the properties of ferroelectric films have been restricted by available substrates. Through controlled substrate engineering, often overlooked in the growth of thin films, we have achieved  $\epsilon_r$  and tunability at room temperature in  $SrTiO_3$  films with properties comparable to bulk  $SrTiO_3$  at cryogenic temperatures. In addition to radically enhanced dielectric properties, we expect other ferroelectric properties (including pyroelectric, piezoelectric and nonlinear optical) of  $SrTiO_3$  to be accessible at room temperature through the application of appropriate homogeneous strain.

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## Bulk glasses and ultrahard nanoceramics based on alumina and rare-earth oxides

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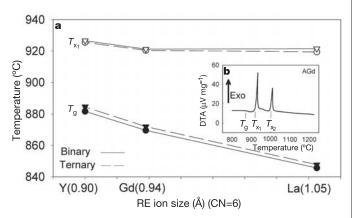
Although often regarded as a network-former in conventional silicate glasses, Al<sub>2</sub>O<sub>3</sub> alone cannot be obtained as a bulk glass. Until now, glasses comprising continuously linked [AlO<sub>x</sub>] polyhedra have been prepared in only a few systems under very fast cooling conditions, which limits their dimensions to a few millimetres<sup>1-3</sup>. Yet it is desirable to prepare bulk, or monolithic, alumina-rich glasses, with the prospect of superior mechanical, chemical and optical properties<sup>4</sup>. Here we report a novel process for preparing very-high-alumina glasses and nanoscale glassceramics. Fully dense bulk articles in net shape are obtained through viscous sintering of glass microbeads. Additional heat treatment of the consolidated glasses leads to fully crystallized transparent glass-converted nanoceramics with a hardness similar to that of alumina. This method avoids the impracticably high applied pressures (more than 1 GPa) that have been required in most cases to prepare nanocrystalline ceramics by sintering, owing to the concurrent nature of densification and grain growth under pressureless conditions<sup>5,6</sup>. The reported techniques can be

# extended to form glasses and nanoceramics in other oxide systems that do not include a conventional glass-forming component.

Elemental and oxide melts lacking conventional glass-formers such as sulphur or silica are prone to crystallization during slow cooling. To form glasses they must be 'kinetically frozen' by rapid quenching, as originally shown for metals<sup>7</sup>. Typically, slower cooling rates can be used for multicomponent eutectic compositions in which ratios of glass transition temperatures  $T_g$  relative to the melting point  $T_m$  are higher<sup>8,9</sup>. For example, Al<sub>2</sub>O<sub>3</sub>, a reluctant glass former, necessitates quenching rates as high as  $10^7$  K s<sup>-1</sup> to retain an amorphous state<sup>10,11</sup>. However, when alloyed in eutectic proportions with other oxides, notably CaO or RE<sub>2</sub>O<sub>3</sub> (where RE stands for rare earth), glasses can be generated at cooling rates of less than  $10^3$  K s<sup>-1</sup> (refs 3, 12, 13). These rates are nevertheless still too high to obtain bulk (more than 1 cm) glasses, limiting the achievable forms to thin films, ribbons, fibres and small spheres.

Sintering of conventional glass frit into coherent, dense, bulk forms is a well-known method in which free surfaces are eliminated by viscous flow at temperatures above  $T_{g}$ . For glasses that do not devitrify, there is little restriction on the sintering temperatures. However, many quenched glasses crystallize rapidly at temperatures  $T_{\rm x}$  when the supplied thermal energy mobilizes the structure and the latent heat previously trapped during quenching is released. The working temperature of such glasses is thus restricted to between  $T_{g}$ and  $T_x$ . The successful exploitation of this kinetic window,  $\Delta T_x =$  $T_{\rm x} = T_{\rm x} - T_{\rm g}$ , was instrumental in the development of bulk metallic glasses from glassy powders a decade ago<sup>14</sup>, but it had not been applied to non-silicate oxides. However, thermal analysis data indicate that a sizable window of  $\Delta T_x$  exists in a rare-earth–alumina system, and 'jelly-like' formability of Al2O3-Gd2O3 glass fibres, when heated inside the  $\Delta T_x$  regime, has been reported<sup>15</sup>. Here we show that the compositional control of this kinetic window provides an easy path to the preparation of bulk glasses and nanocrystalline glass-ceramics in a variety of non-conventional glass-forming oxide systems.

Alumina–rare-earth oxide systems (Al<sub>2</sub>O<sub>3</sub>–RE<sub>2</sub>O<sub>3</sub>) were chosen for this study because of their technological importance. Binary



**Figure 1** Effect of rare-earth ion size on  $\Delta T_x$ . **a**, Glass transition ( $T_g$ ) and crystallization ( $T_x$ ) temperatures of binary (solid lines) and ternary (dashed lines) glasses as a function of the ionic radius of the rare-earth (RE) cation. CN, coordination number. **b**, DTA trace of 77 Al<sub>2</sub>O<sub>3</sub>-23 Gd<sub>2</sub>O<sub>3</sub> (mol.%) glass heated at 10 °C min<sup>-1</sup>. Although two exothermic events— $T_{x1}$  and  $T_{x2}$ —were frequently observed in these glasses, only the first ( $T_{x1}$ ) reflects the crystallization event, whereas  $T_{x2}$  is thought to be caused by a liquid–liquid transition from a metastable high-density amorphous phase to more stable low-density amorphous phase<sup>27</sup>. In ternary liquids, the  $T_{x2}$  peak was essentially absent, which might have been caused by higher viscosities of these liquids and the retention of a single (high-density amorphous) phase during cooling. Throughout the article,  $T_x$  is identified with  $T_{x1}$ .